

Lecture

3

ECE M216A

Logic Design

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Agenda

- **Logic design concepts**
 - Fast vs. slow inputs
 - Transmission gates
- **More delay models**
 - Simulation-based
 - Library models
- **Optimal gate sizing**
 - Min delay
 - Delay $>$ min delay

Faster Inputs

越靠近 output 的越快 (faster)

- Higher input of a stack is faster (in_2 is faster than in_1)

- V_x pre-discharged

Faster input

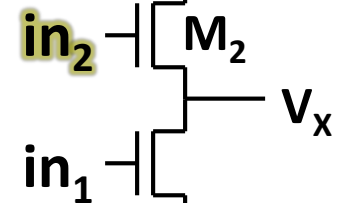
假如 in_2 先到,

- Also body effect on M_2 charge V_x , 从而 V_{T2} 上升, 因此要更长时间去 discharge

- Use higher inputs for the LATE arrivals

- Synthesis tools do this

both input is V_{out} 这也有个 Capacitor



① 先 in_1 , 可以先把 V_x discharge to ground

so V_x discharge to 0

② in_2 , 需要为 output capacitor

假如先 in_2 , 他会先

需要再次 discharge V_x 充电, 从而导

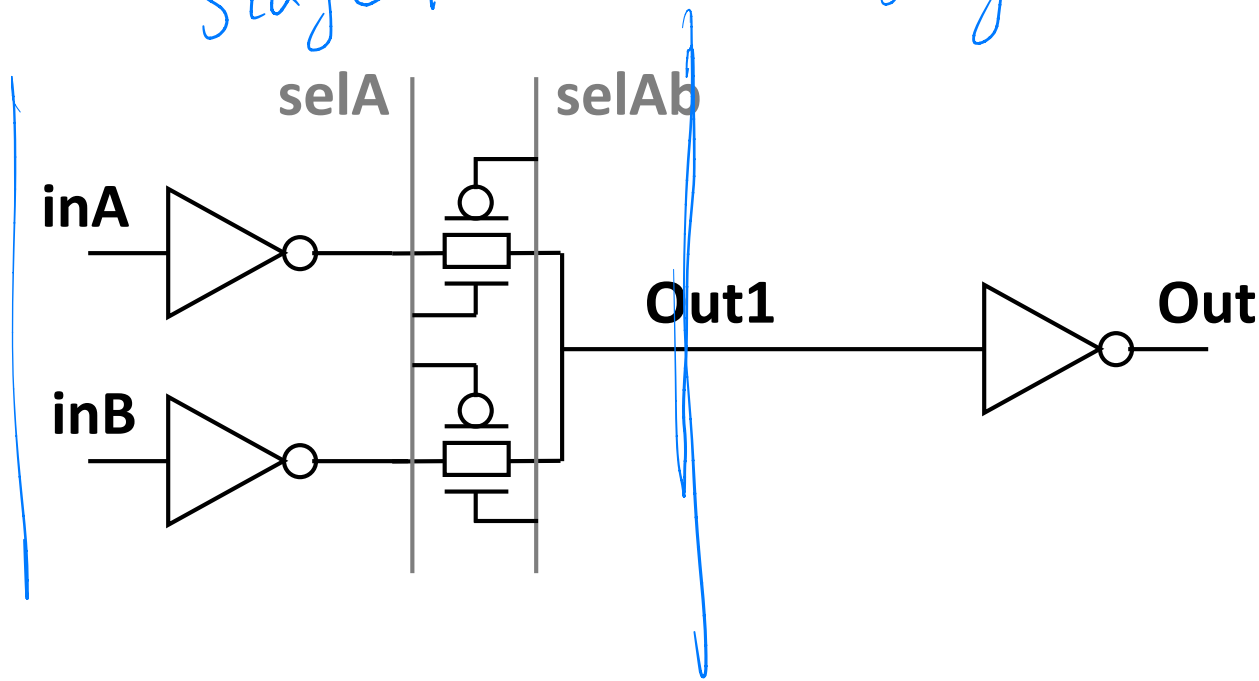
Mixing Static CMOS & Transmission Gates

- Static CMOS gates drive a TG switch network
- Output of network drives a static CMOS gate
- Example: a 2:1 Mux

$$t_p = t_{p1} + t_{p2}$$

stage 1

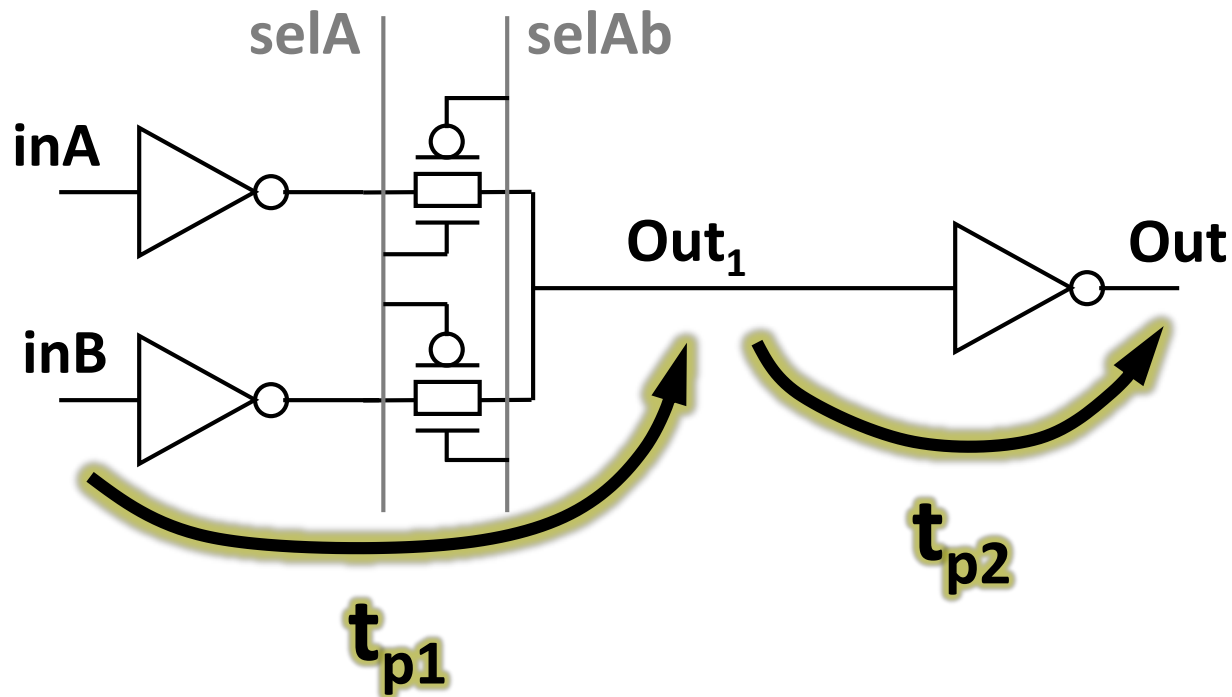
stage 2



Example 3.1: Transmission Gate Delay

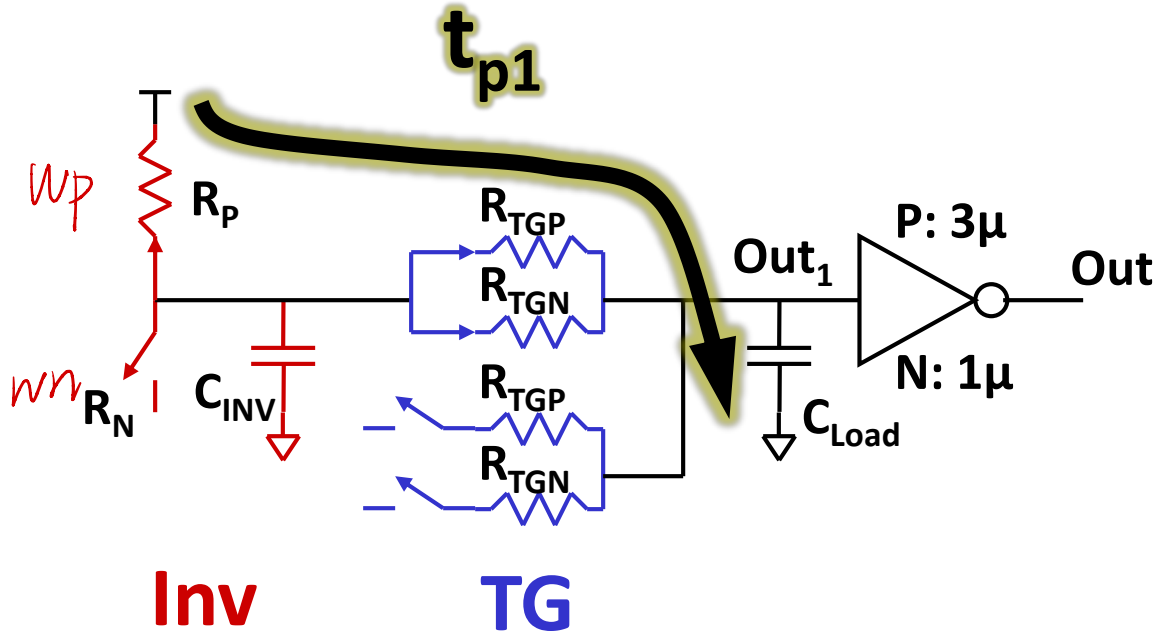
- Delay depends on the gate that drives the switch
- Example: path B selected, Out_1 pulling up

$$t_p = t_{p1} + t_{p2}$$



Modeling the Delay

- Focus on the 1st (compound) stage
(2nd stage is a simple inverter)



Assume:

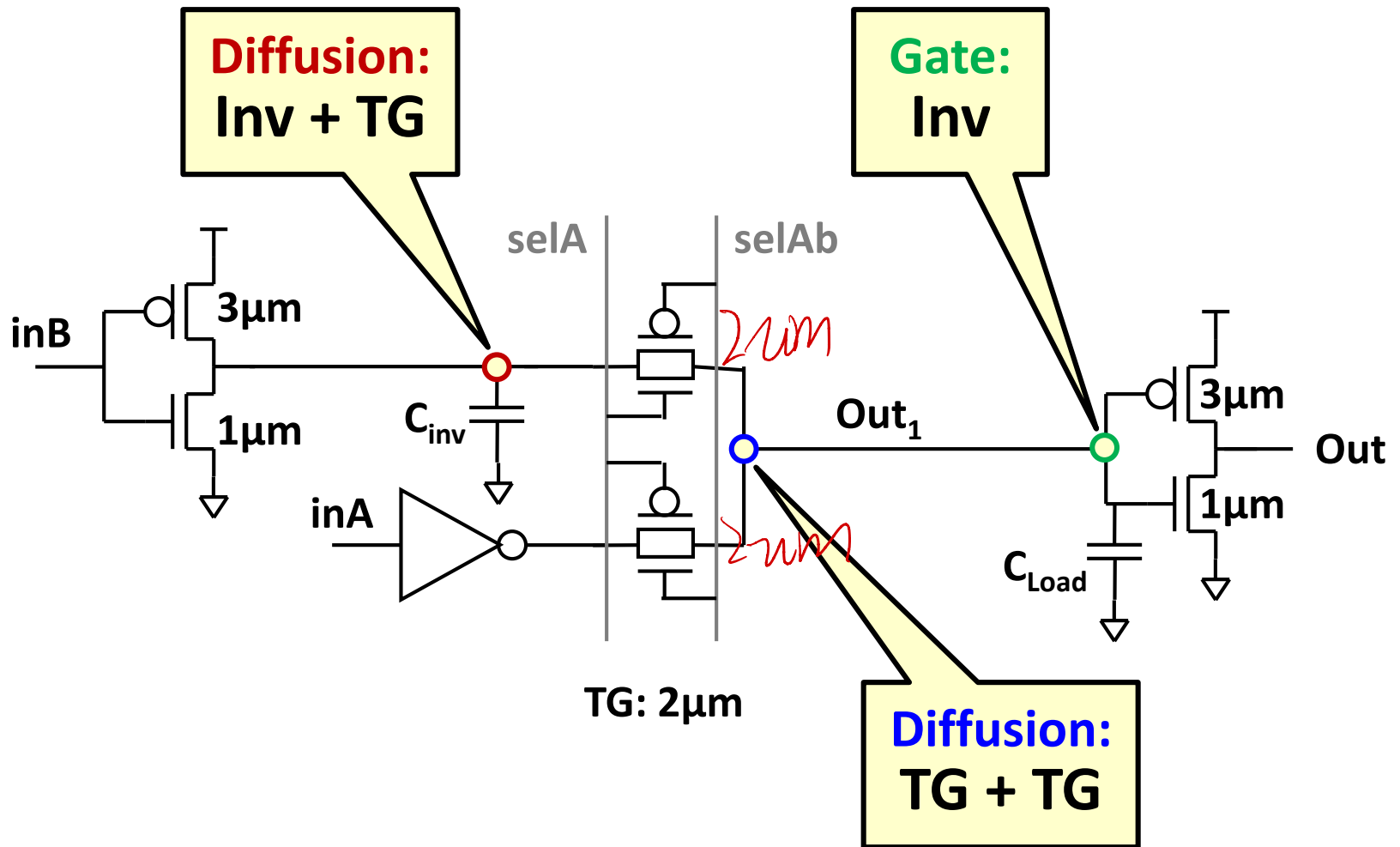
Inverters

- $W_p = 3 \mu m$
- $W_n = 1 \mu m$

Trans. Gates

- $W_p = 2 \mu m$
- $W_n = 2 \mu m$

Capacitance Components



Calculate the Capacitances

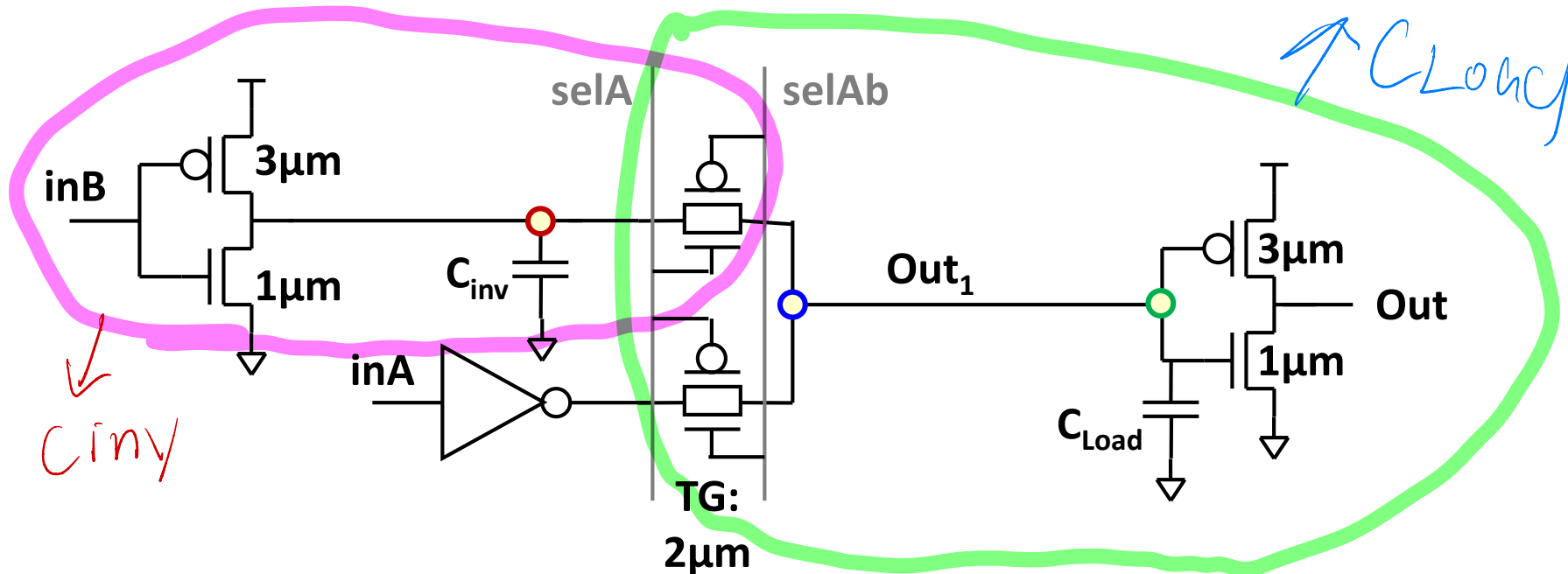
$$C_{\text{inv}} = \overbrace{(3\mu + 1\mu) \cdot 1.5\text{f}}^{\text{Inv}} + \overbrace{(2\mu + 2\mu) \cdot 1.5\text{f}}^{\text{TG}} = 12\text{ fF}$$

$$C_{\text{Load}} = \underbrace{(2 \cdot 2\mu) \cdot 1.5\text{f}}_{\text{TG}} + \underbrace{(2 \cdot 2\mu) \cdot 1.5\text{f}}_{\text{TG}} + \underbrace{(3\mu + 1\mu) \cdot 2\text{f}}_{\text{Inv}} = 20\text{ fF}$$

diffusion

Assumptions:

- $C_D = 1.5\text{ fF}/\mu\text{m}$
- $C_G = 2\text{ fF}/\mu\text{m}$

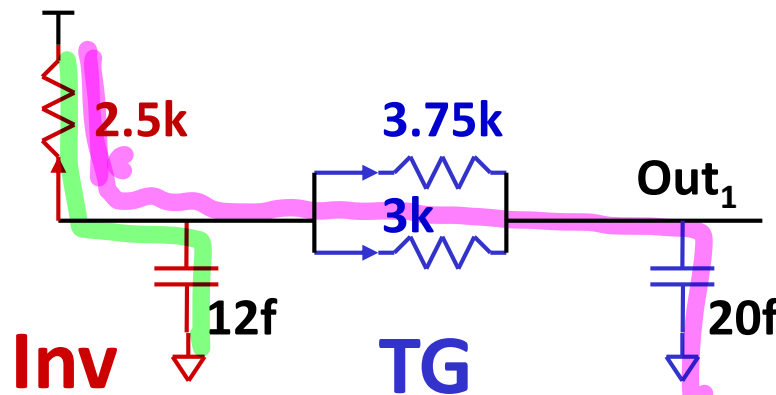


Calculate RC Time Constant τ_1

- $R_p = 7.5 \text{ k}\Omega\text{-}\mu / 3 \mu = 2.5 \text{ k}\Omega$
- $R_{TGP} = 7.5 \text{ k}\Omega\text{-}\mu / 2 \mu = 3.75 \text{ k}\Omega$
- $R_{TGN} = 6 \text{ k}\Omega\text{-}\mu / 2 \mu = 3 \text{ k}\Omega$

Assumptions:

- $R_{ND} = 3 \text{ k}\Omega\text{-}\mu\text{m}$
- $R_{NU} = 6 \text{ k}\Omega\text{-}\mu\text{m}$
- $R_{PU} = 7.5 \text{ k}\Omega\text{-}\mu\text{m}$
- $R_{PD} = 15 \text{ k}\Omega\text{-}\mu\text{m}$



select this "smart" worst case

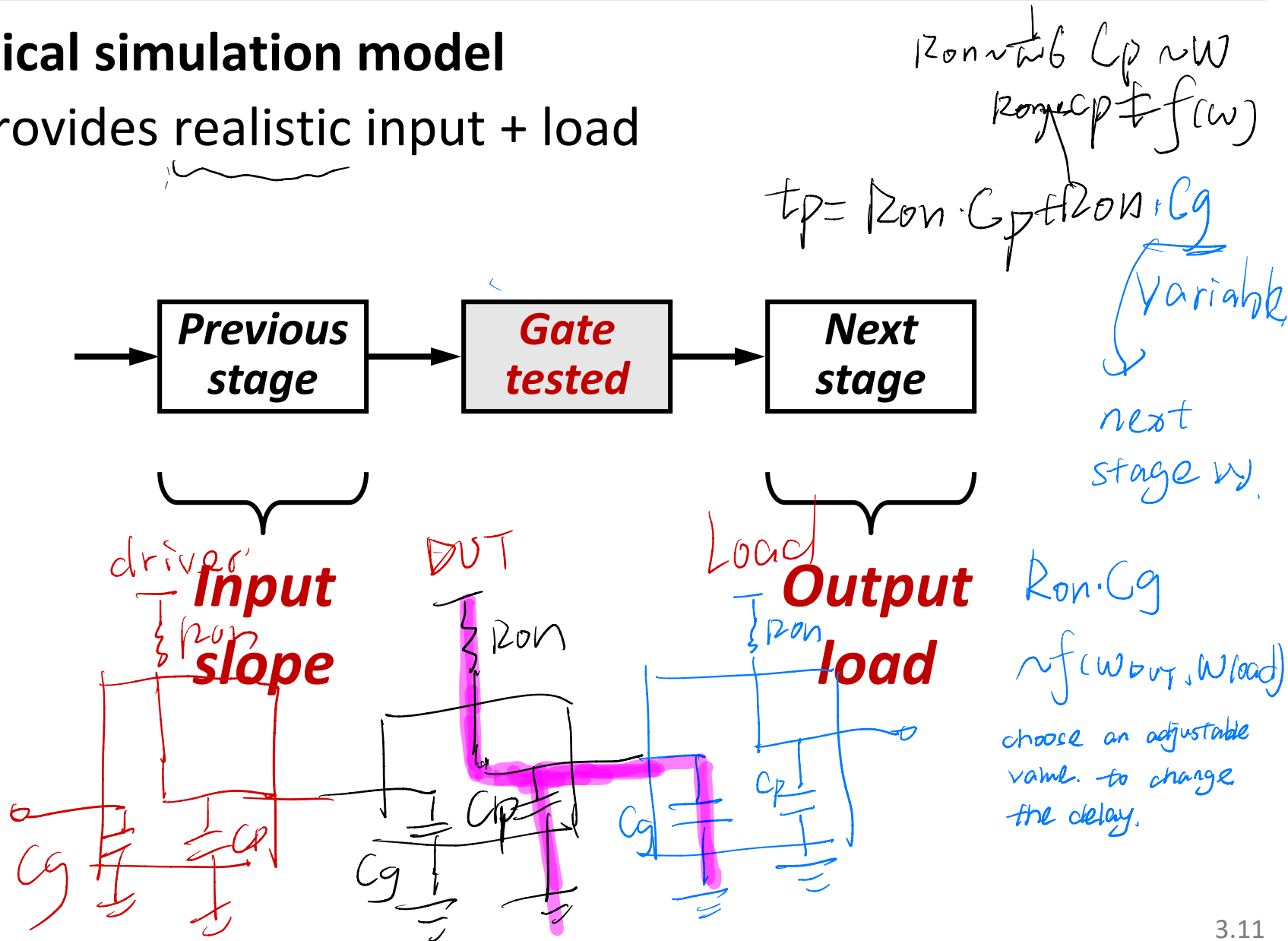
$$\tau_1 = 2.5\text{k} \cdot 12\text{f} + (2.5\text{k} + 3.75\text{k} \parallel 3\text{k}) \cdot 20\text{f} = 113\text{ps}$$

absolute worst case.

Simulation-Based Delay Model

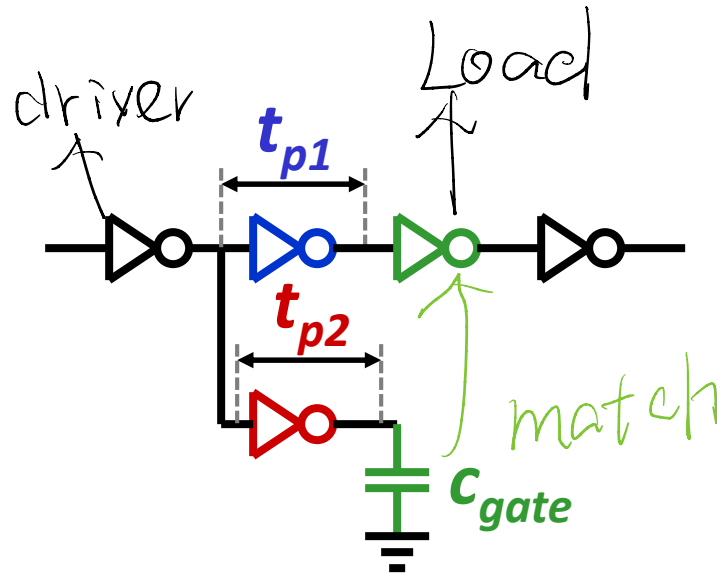
Simulation-Based Parameter Extraction

- Typical simulation model
 - Provides realistic input + load



Extracting C_{gate} by Simulation

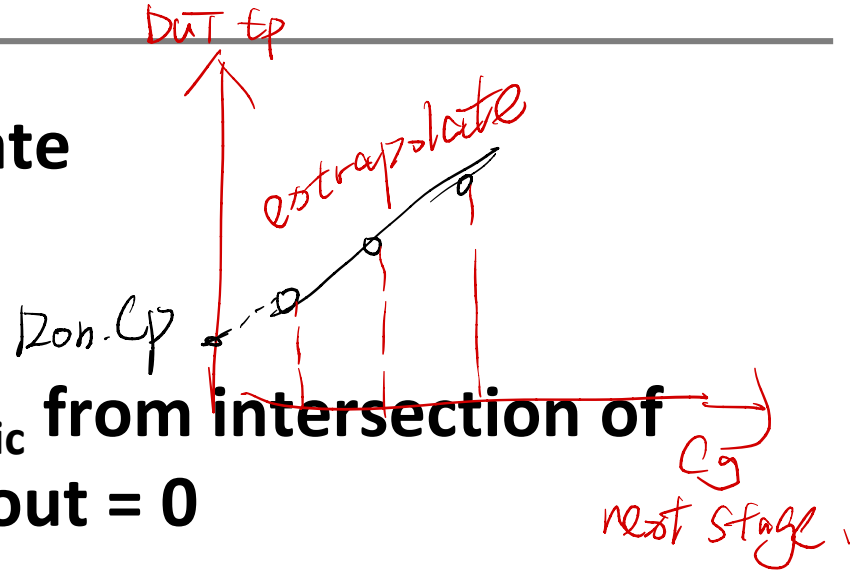
Curve-fitting:
Sweep C_{gate}
until $t_{p1} = t_{p2}$



- $t_{p1} = t_{p2} \rightarrow C_{gate}$ is equivalent cap of the **green** gate
- **Limitations:** the model depends on signal rise times, voltage, temperature, process parameter variations

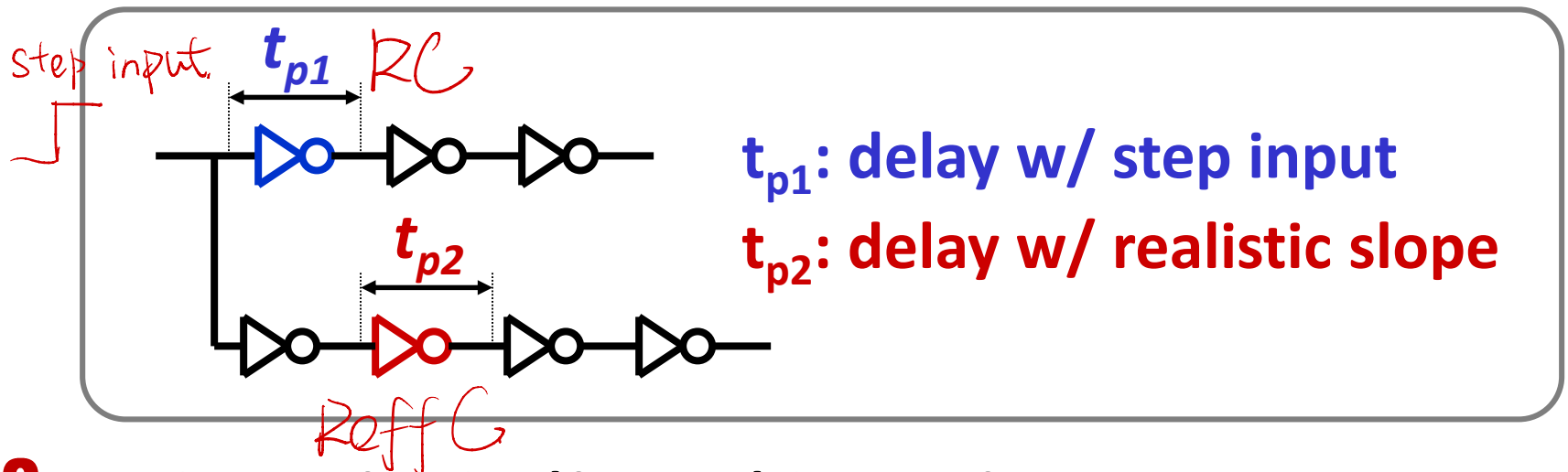
Extracting $C_{\text{parasitic}}$ by Simulation

- 1 • Delay of the unloaded gate
 - Beware of signal slopes
- 2 • Another way: find $C_{\text{parasitic}}$ from intersection of delay(fanout) line at fanout = 0
- 3 • Play with AS, PS, AD, PD model parameters
 - $AS = AD = PS = PD = 0$ [overlap + junction caps]
- C_{gate} & C_{par} for t_{pLH} and t_{pHL} are different [WHY?]
 - For delay analysis, we use the average value



Extracting R_{eff} by Simulation

- 1 • Use the delay formula to find R_{eff}
 - $R_{\text{eff}} = t_{p,\text{gate}} / (0.69 C_{\text{gate}})$
 - Reminder: set AS, AD, PS, PD to 0!



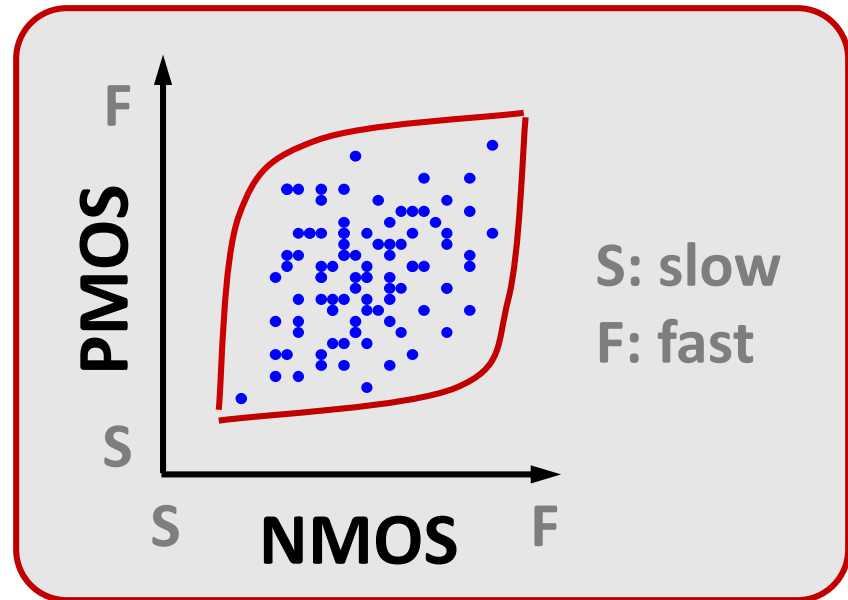
- 2 • Slope of delay(fanout) line $\propto \text{fanout} \cdot R_{\text{eff}} \cdot C_{\text{gate}}$
- R_{eff} for transistor stacks could be similarly found
 - Make sure you factor in the parasitic cap

The “Flow”

- **Hand design**
 - Simple RC models provide **intuition** about circuits
 - Tradeoff analysis
 - Dominant effects
 - Reasonable starting point in the design process
 - Run simulations to refine the model
- **Simulation** (to confirm your intuition)
 - If the simulation results are way off, there is a bug (check schematics, simulation files, your models)
 - Don't forget the corners

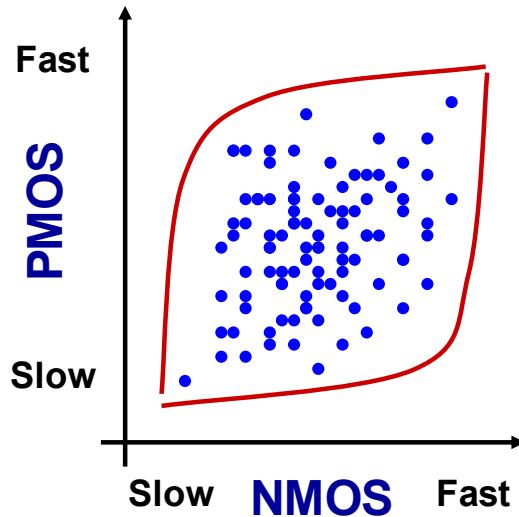
Process Variations

- **Not all devices (primarily transistors) are created equal**
 - Even if they nominally have the same exact drawing
 - Two on the same die (wafer, lot) can differ
- **Variations cause transistors to have different V_T and μ , speeding up (F) or slowing down (S) the devices**
 - Doping conc. (μ)
 - W/L
 - t_{ox}

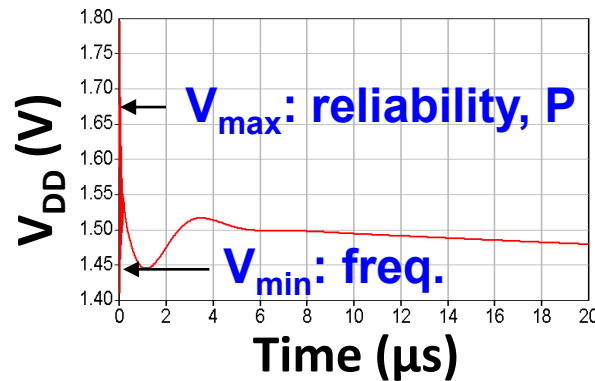


More Corners (PVT Variation)

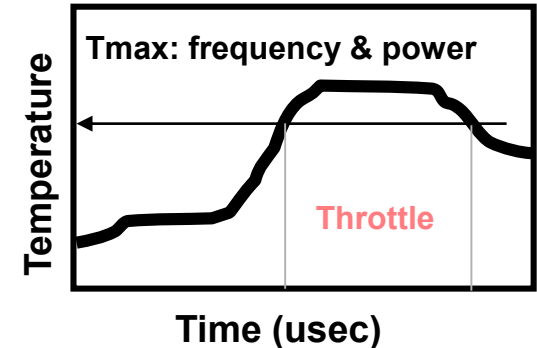
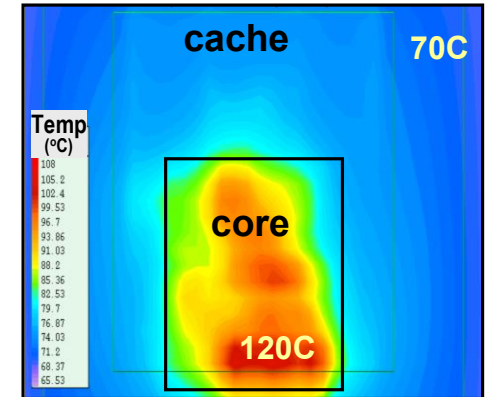
Process



Voltage



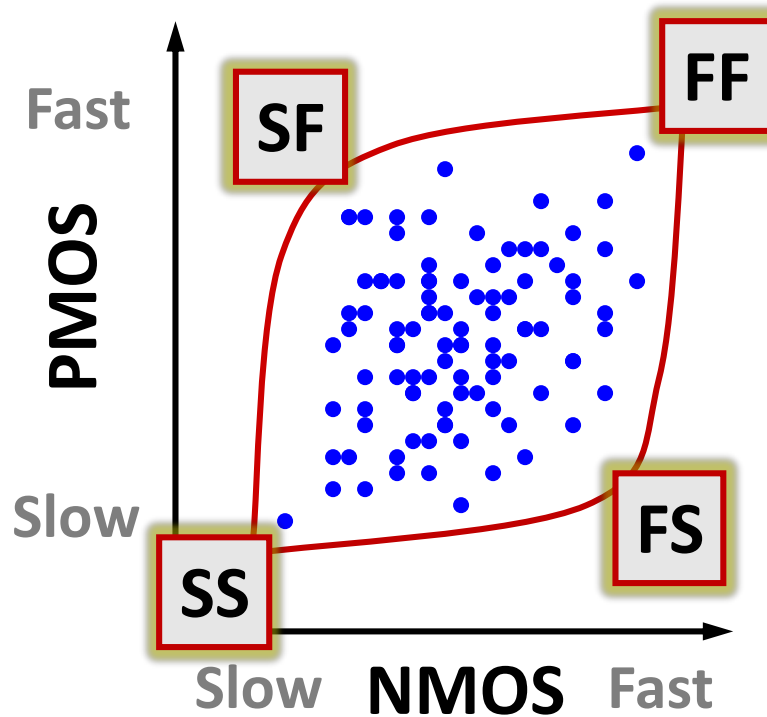
Temperature



- Typically, given corner parameters for devices
 - Characterize effective parameters across corners

$$\mu = \mu_0 \cdot \left(\frac{T_0}{T} \right)^{1.5}$$

Process Corners Combined



Includes:

- Process
- Voltage
- Temp variations

S: low V_{DD} , high T (t_{setup})

F: high V_{DD} , low T (t_{hold})

Delay and Transition Time

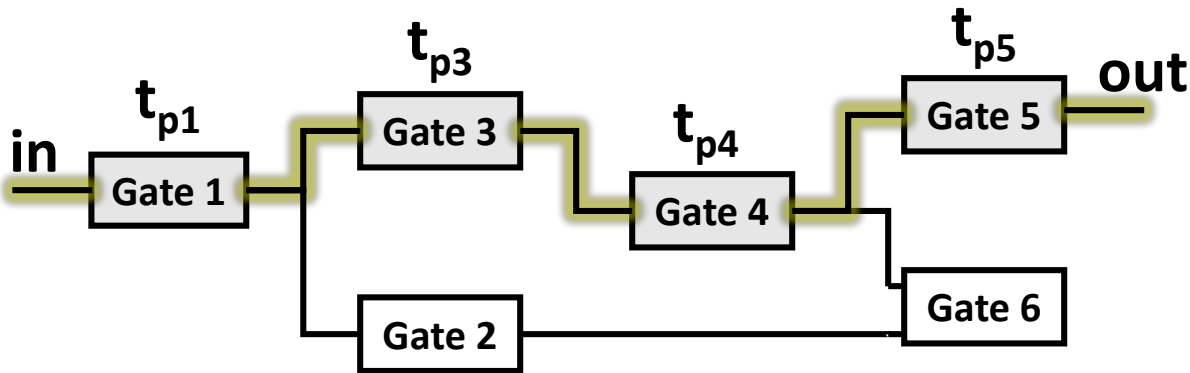
- Gate delay is approximated as RC elements
- The transition time is proportional to the same RC
 - Using ideal RC, the 10-90% is roughly $2.2RC$
- For a gate (inverter) driving another gate,
 - Transition time is roughly $2t_{\text{DELAY}}$
 - Valid only for RC network
 - [What would happen in an inductive network?]
- Useful for modeling noise coupling
 - Aggressor transition time determines injected noise

Multi-Stage Gate Delay

- **Static CMOS:** total delay = sum of stage delays

$$t_{total} = \sum_n t_n$$

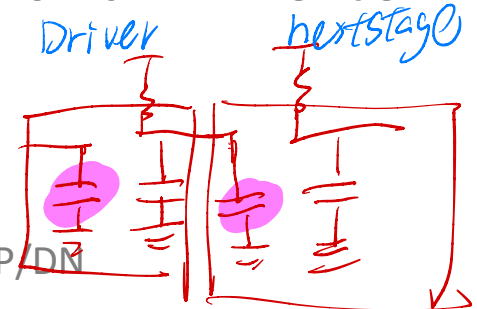
- The R of the *current stage*
- The C of the subsequent gate(s)
next stage



$$t_{total} = t_{p1}(R_1, C_3, C_2) + t_{p3}(R_3, C_4) + t_{p4}(R_4, C_5, C_6) + t_{p5}(R_5, C_L)$$

Fan-In and Fan-Out

- **Fan-In:** the number of inputs (logic gate)
 - An indication of the input load that the gate presents to a predecessor gate
 - Because the series stack is roughly the number of inputs
 - Later we will use **Logical Effort** to embed this concept
- **Fan-Out:** effective output load (relative to Inv) *ratio of C_{gate} of next stage and C_{gate} of Driver*
 - An indication of the loading (gate type dependent)
 - Useful to normalize the loading to C_{gate} of an inverter with equal drive strength as the gate
 - $FO = C_{LOAD} / C_{INV}$
 where $C_{INV} = C_0'(W_P + W_N)$ and $R_{INV} = R_{PULL_UP/DN}$



Example 3.2: Fanout Calculation

NAND gate driving 5 equal NAND gates

- NAND gate: $W_p = 5$, $W_n = 5$

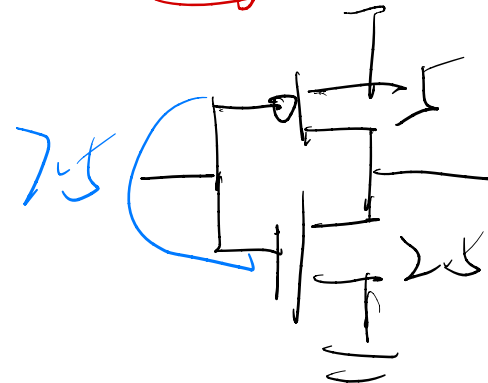
$F_o = \frac{50}{10} = 5$

- Total input width = 10
- Total load gate width = $5 \cdot 10 = 50$

- Equivalent Inv: $W_p = 5$, $W_n = 2.5$

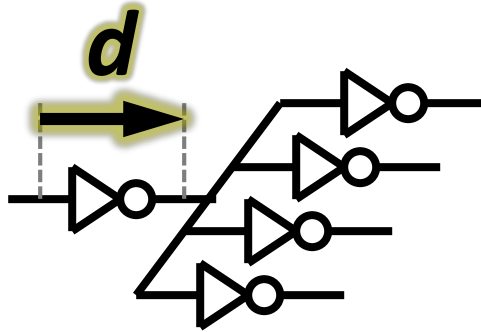
- Equivalent (in terms of PU and PD strength)
- Total gate width = 7.5

- Fanout = $50/7.5 = 6.6$



Another Metric: **FO4 Inverter Delay**

- Measures quality of design independent of technology



Cadence 90nm technology:

FO4 = 33ps

Ring Osc Stage = 13ps

Mini assignment:

Simulate FO4 delay
in 32nm (slide 2.34)

Model Used in Cell Libraries

Propagate two quantities:

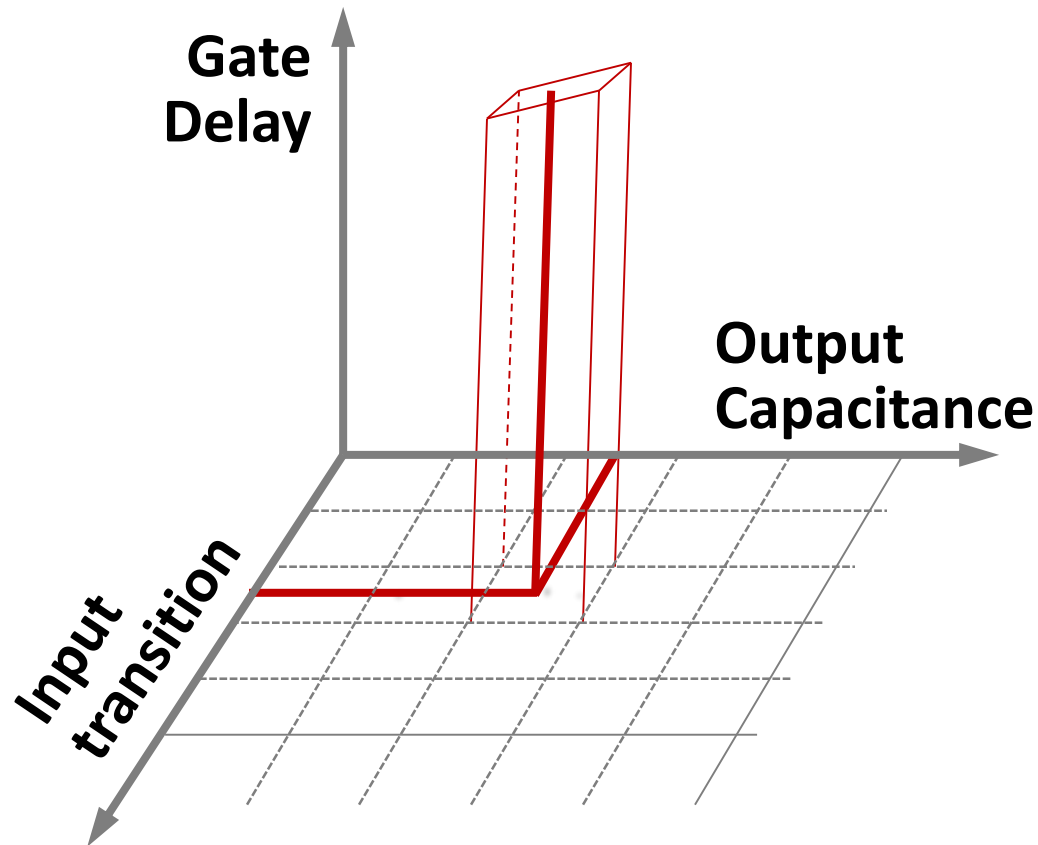
- Delay
- Signal slope

Modeled as linear or table lookups

Gate Delay Estimation

- Depends on **transistor sizes, input signal slew, output capacitive load and PVT conditions**
- **For each PVT, timing library is provided by vendor**
 - Delay, output slew, dynamic and static power are characterized for different input slew and output loads
- **Characterization values are stored as 2-D look-up tables**
 - Output delay = $f(\text{input slew, output load capacitance})$

Gate Delay Estimation



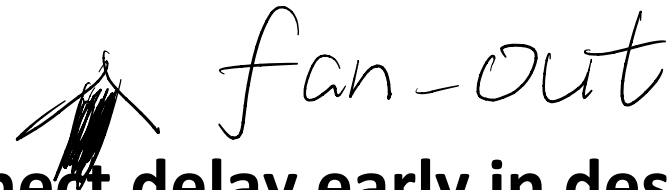
Interpolation with 4 points

Design Problem: **Interconnect Delay**

- Timing assumption during pre-layout synthesis **widely differs** from the post-layout reality
- This happens because the **interconnect delay** **dominates** the overall delay in scaled technologies
- As a result, **timing closure** becomes a challenge

CAD Problem: **Interconnect Delay**

- New industry trends = new IC design flows
- The major contributing factors:
 - Interconnect delay and area
 - The number of metal layers
 - Planning requirements
- Need to consider interconnect delay early in design
- A few techniques for reducing interconnect delay:
 - Chip-level signal planning
 - Over-the-Cell routing

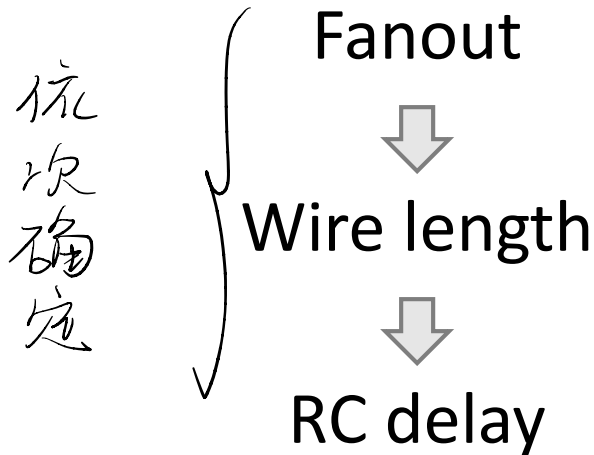


Wire Load Models (WLMs)

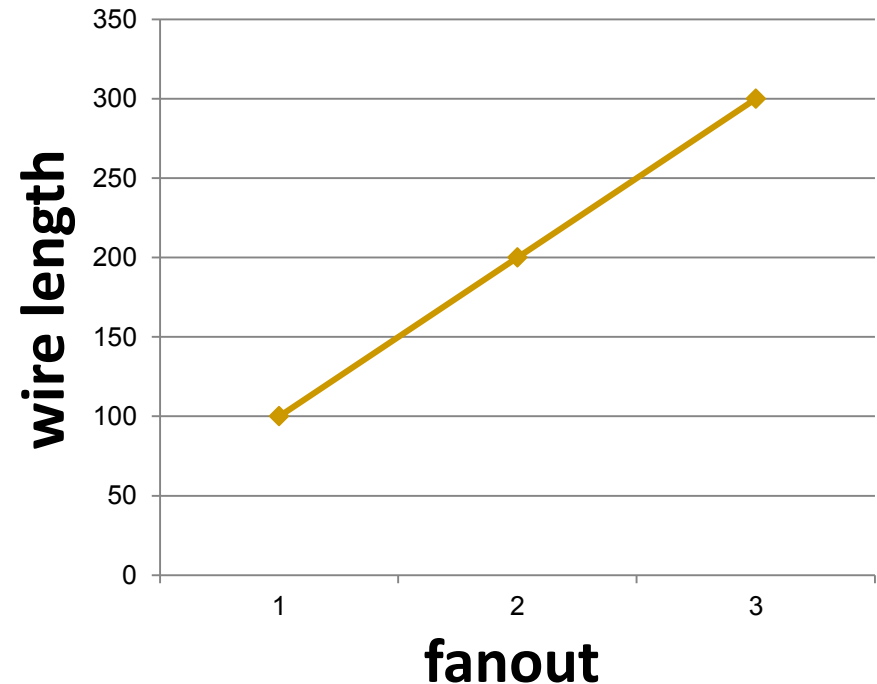
- **In the absence of physical design information DC uses statistically generated WLMs to estimate wire lengths**
 - WLMs provide a fanout vs. length relationship
- **Interconnect delay estimation:**
 - By knowing fanout, estimate the wire lengths
 - Next, given unit-length R and C and the estimated length, estimate R and C to give an estimated delays
- **Note:** WLMs are area dependent
 - Unit-length R and C increase with area

Example WLM

```
wire_load('30x30') {  
  capacitance : 3.0 ; /* C per unit length */  
  resistance : 30.0 ; /* R per unit length */  
  area : 1.5 ; /* area per unit length */  
  slope : 1.5 ; /* extrapolation slope */  
  fanout_length(1,1) ; /* fanout/length pairs */  
  fanout_length(2,2.2);  
  fanout_length(3,3.3);  
  fanout_length(4,4.4); }
```



**Model from a library
compiler (LC) source file:**

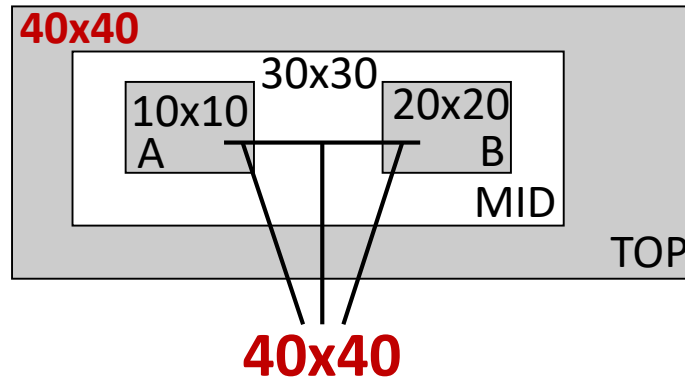


Courtesy: Synopsys

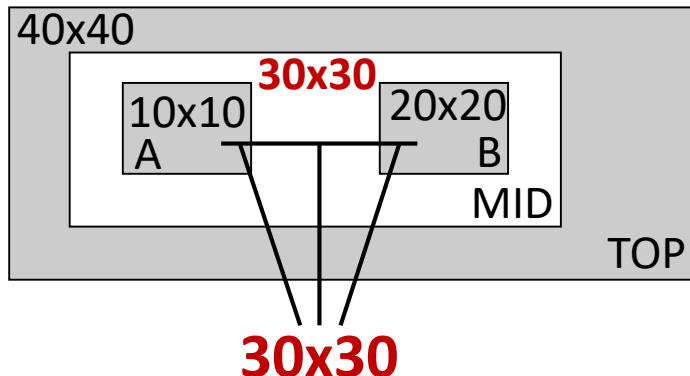
Hierarchical Wire Load Models

DC supports **3 modes** for nets that cross hier. boundaries

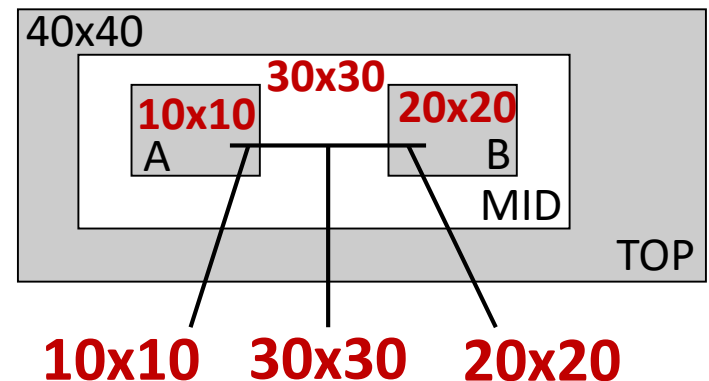
Mode = **top**



Mode = **enclosed**



Mode = **segmented**



Courtesy: Synopsys

Speed Optimization via Gate Sizing

Speed Optimization via Gate Sizing



- **Gate sizing basics**

- P:N ratio
- Complex gates
- Velocity saturation
- Tapering

- **Developing intuition**

- Number of stages vs. fanout
- Popular inverter chain example

Basic Gate Sizing Relationships

- Rise and fall delays are determined by the pull-up and pull-down “strength”
 - Besides the W/L , strength depends on μ , V_T
 - PMOS is weaker because of lower μ_p
 - Larger P network than N network
- Increasing size of gate can reduce delay
 - $R_{on} \propto 1/W$
 - **BUT** it can slow down the gate driving it
 - $C \propto W$. So be careful!

P:N Ratio for “Equal” Rise and Fall Delay

- Good to have $t_{pHL} \approx t_{pLH}$
 - Don't need to worry about a worst-case sequence
 - Size P's to compensate for mobility
 - C_{ox} , V_T , L are roughly the same

$$R_{on} \propto \frac{1}{I} \propto \frac{1}{\mu W}$$

- Make $R_p = R_n$

- $R_n/R_p = 1$

$$(\mu_p W_p / \mu_n W_n = \beta/k)$$

$$k = \frac{\mu_n}{\mu_p} = \beta = \frac{\mu_p}{\mu_n}$$

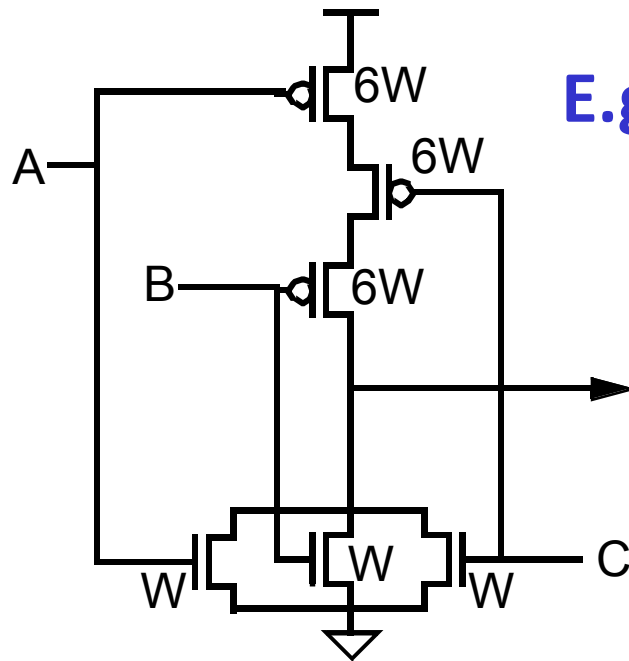
$$t_{pLH} = t_{pHL}$$

$$\frac{W_p}{W_n} = \beta = k = \frac{\mu_n}{\mu_p}$$

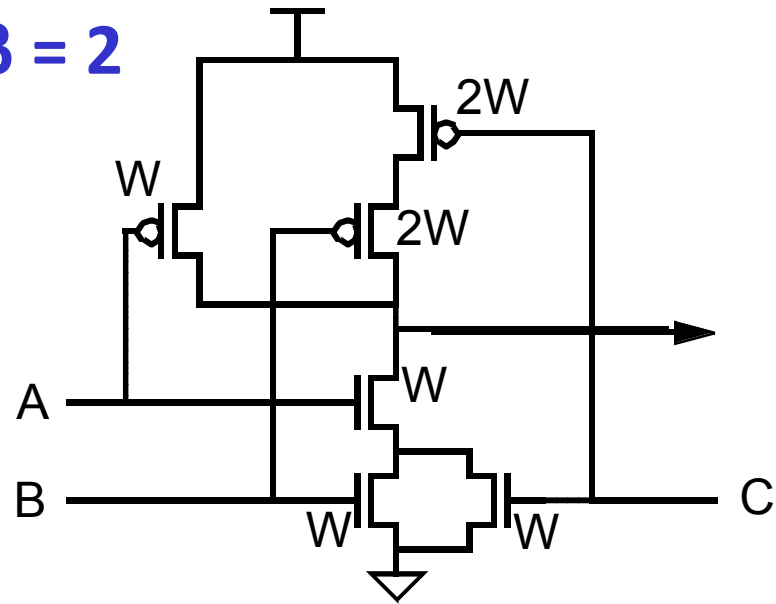
Complex Gate Sizing

Stacking

- **N-stack** series devices need **N times** lower resistance
 - **$N \times \text{Width}$**
- **Make worst-case strength of each path equal**
 - Multi-input transition can result in stronger network
- **Long series stacking is VERY bad**

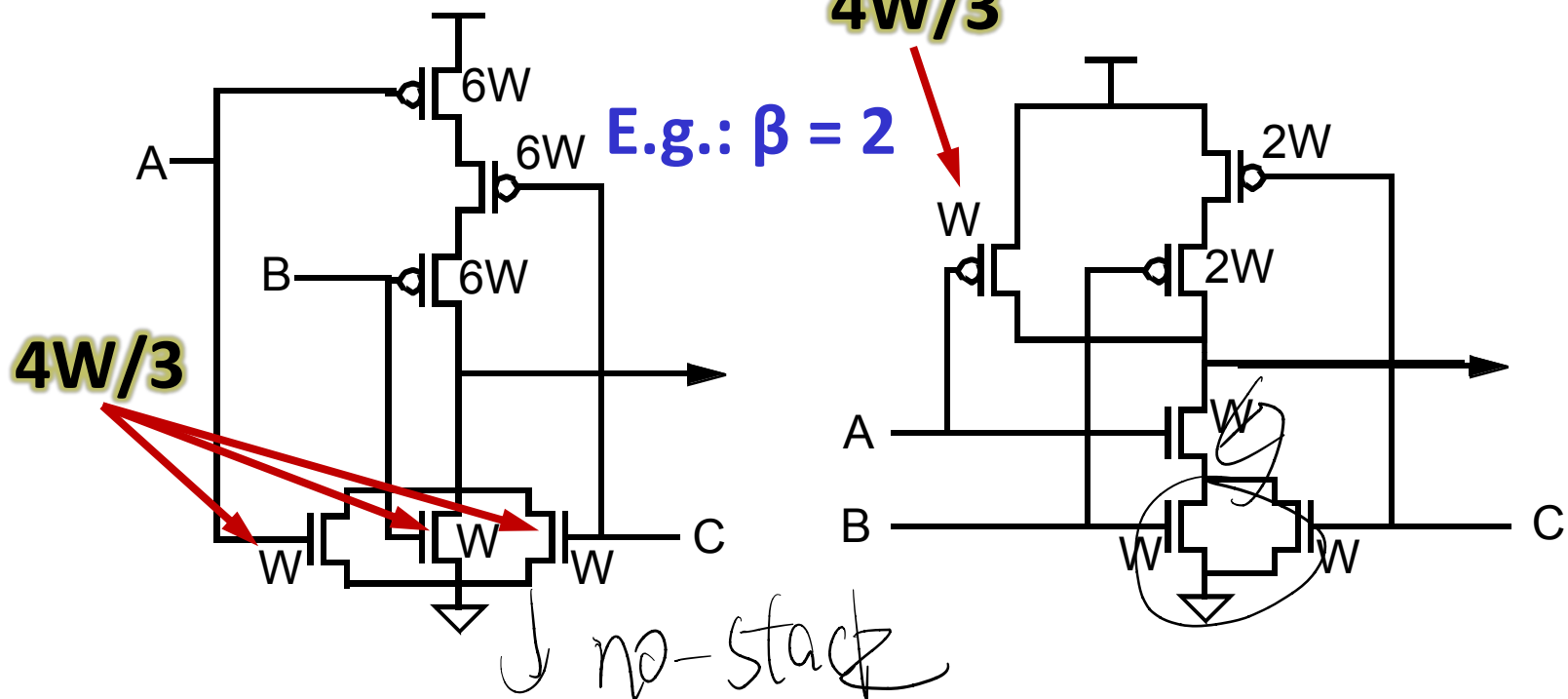


E.g.: $\beta = 2$



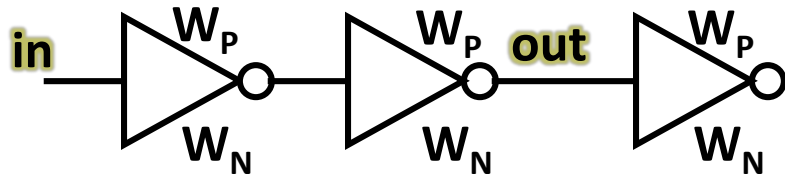
Accounting for Velocity Saturation

- Series stacking is actually less velocity saturated
 - If we use $R_{\text{no_stack}} = (4/3)R_{\text{stack}}$
 - Adjust the size of non-stacked devices to account for velocity saturation



P:N Ratio for Minimum Delay?

- Delay of 2 inverters:



Assumptions:

- $R_{PDRV} \sim R_0' / W_P \mu_P$
- $R_{NDRV} \sim R_0' / W_N \mu_N$
- $C_G \sim C_0(1 + W_P/W_N)$

- $t_p = t_{p1} + t_{p2} = R_0'(1/W_P \mu_P + 1/W_N \mu_N) C_0(1 + W_P/W_N)$

- $t_p = t_N(1 + 1/k\beta)(1 + \beta)$

- $dt_p/d\beta = 0$
 $= t_N(1 - k/\beta^2)$



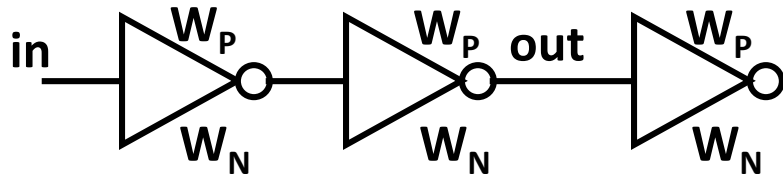
$$\text{Min } (t_{pLH} + t_{pHL})/2$$

$$\frac{W_p}{W_n} = \beta = \sqrt{k} = \sqrt{\frac{\mu_n}{\mu_p}}$$

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P:N Ratio for Equal/Minimum Delay

- Delay of 2 inverters:



$$t_{pLH} = t_{pHL}$$

$$\frac{W_p}{W_n} = \beta = k = \frac{\mu_n}{\mu_p}$$

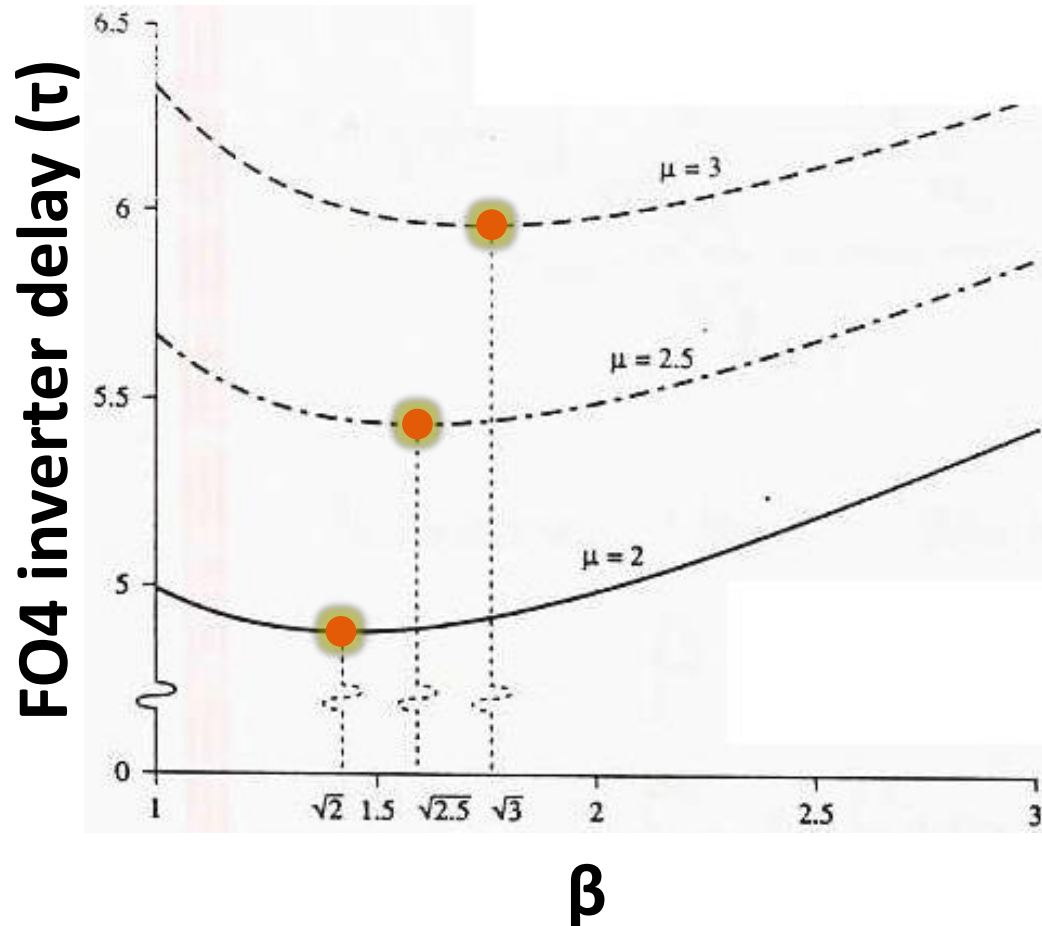
**NMOS: more drive
for a given size, so
it is better to use
more NMOS**

$$\text{Min } (t_{pLH} + t_{pHL})/2$$

$$\frac{W_p}{W_n} = \beta = \sqrt{k} = \sqrt{\frac{\mu_n}{\mu_p}}$$

FO4 Inverter Delay vs. P:N Ratio β

- Optimal $\beta = \sqrt{\mu}$ for minimum delay
 - Curve is relatively flat so not a strong delay tradeoff



An Idea: Tapering

- **C closer to the v-source: less effect on delay**

C₃ most effect on delay

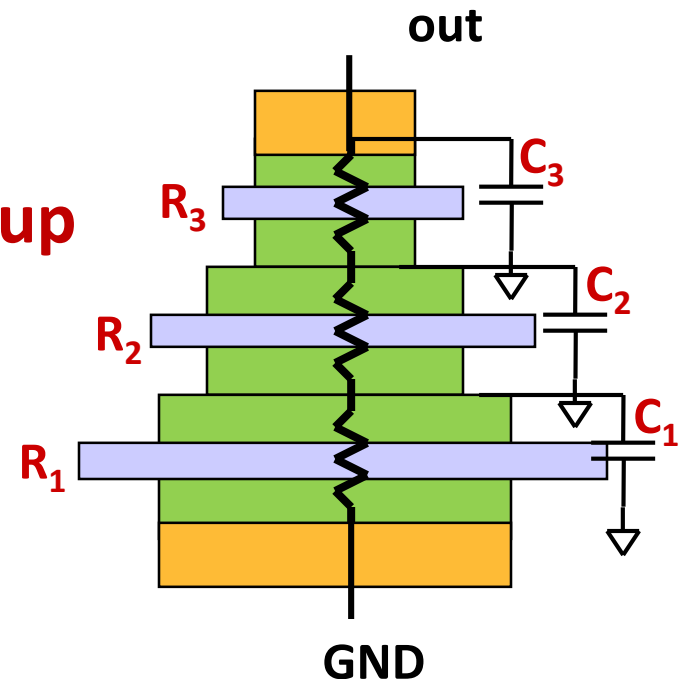
- $N = 2: t_p = R_1(C_1) + (R_1 + R_2)(C_2)$

- C_1 has less effect on delay than C_2

- So **taper stacked devices for speedup**

- Make the bottom ones bigger

- R_1 (many occurrences) has less resistance
- C_3 (multiplying larger R) has smaller capacitance

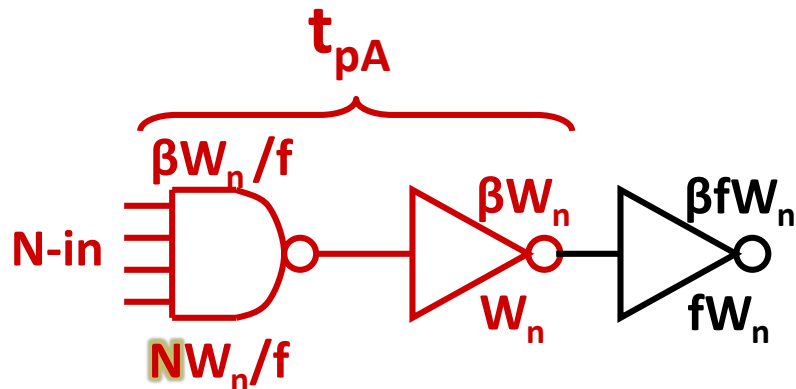


In reality, tapering doesn't win as much because layout is less compact when stacking unequal sized transistors (causing more C)

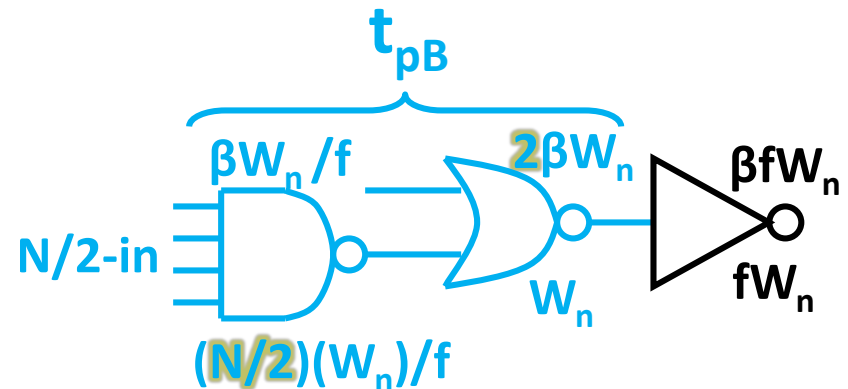
Example 3.3: Gate Design for Min Delay

- Which scenario (A, B) has faster delay?
 - Drive the same output load

A: N-in NAND + INV



B: N/2-in NAND + NOR



Let's analyze building blocks: NAND, NOR, INV

A1: Delay of N-input NAND

Assumptions:

- $C_G = C_D = C_0$ [fF/ μm]
- $R_n = R_0 W_n - \mu\text{m}$



For N inputs:

- $R_1 = \dots = R_N = R_0 / (N W_n / f) = R_i$
- $C_1 = \dots = C_N = N C_0 W_n / f = C_i$

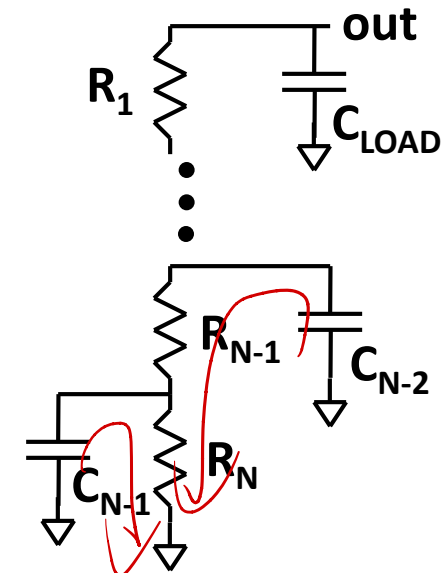


$$R_i C_i = R_0 C_0$$

$$t_p = \sum_{i=1}^{N-1} i R_i C_i + R_{tot} (C_N + N C_0 \frac{\beta W_n}{f} + C_{gate})$$

N-stack NMOS:

$$N \cdot W_n / f$$



A1: Delay of N-input NAND

$$t_p = \sum_{i=1}^{N-1} iR_i C_i + R_{tot} (C_N + NC_0 \frac{\beta W_n}{f} + C_{gate})$$

$$t_p = \sum_{i=1}^{N-1} iR_0 C_0 + R_0 (NC_0 + NC_0 \beta + C_{gate} \frac{f}{W_n})$$

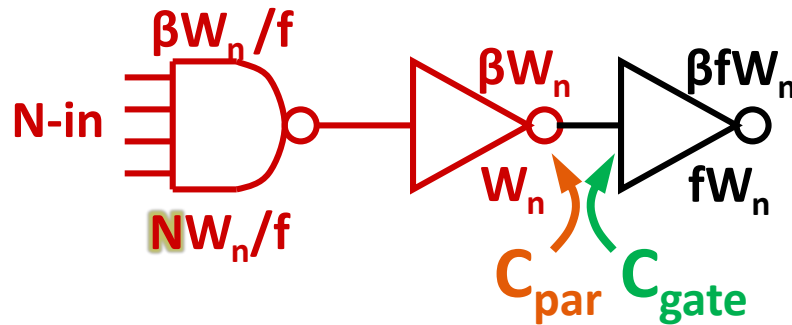
$R_{tot} = \frac{R_0}{W_n f}$ $R_i = \frac{R_0}{i W_n f}$

NMOS PMOS Output

n transistor elements

$$t_p = R_0 C_0 \left(\frac{N(N-1)}{2} + N \right) + R_0 C_0 \left(\beta N + \frac{C_{gate}}{C_0} \frac{f}{W_n} \right)$$

A2: Delay of Inverter

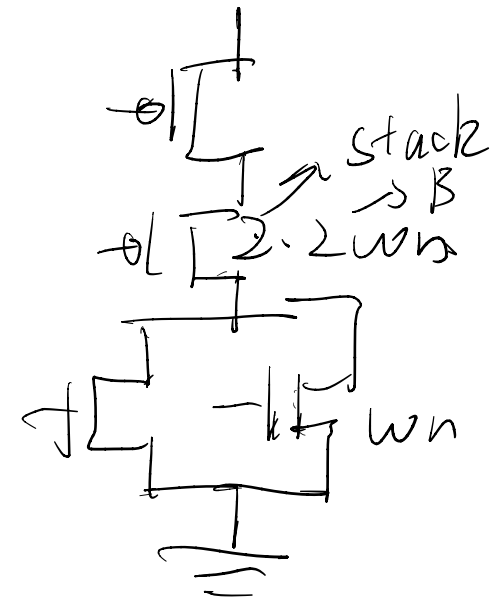
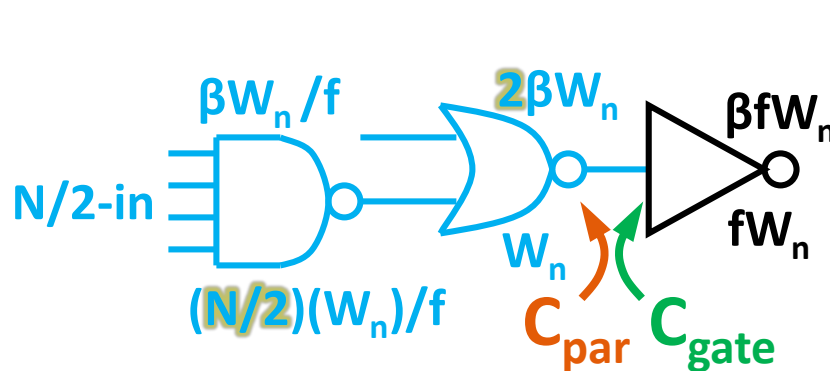


Inverter:

- $R_{INV} = R_0/W_n$
- $C_{L,INV} = C_{par} + C_{gate} = C_0(\underbrace{W_n(1+\beta)}_{\text{orange}}) + \underbrace{f W_n(1+\beta)}_{\text{green}}$
- $t_{INV} = R_0 C_0 (1+\beta)(1+f)$

$$\underbrace{C_{gate,INV} = C_0(W_n(1+\beta))}_{\text{red wavy line}}$$

B2: Delay of NOR2



NOR2:

- $R_{NOR} = R_0 / W_n$
- $C_{L,NOR} = C_{par} + C_{gate} = C_0(W_n(2+2\beta) + f W_n(1+\beta))$
- $t_{NOR} = R_0 C_0(1+\beta)(2+f)$

2 NMOS



$$C_{gate,NOR} = C_0(W_n(1+2\beta))$$

Delay Comparison ($\beta = 2$)

A: N-in NAND + INV

$$t_{pA} = R_0 C_0 \left(\frac{N(N-1)}{2} + 3N + 3f \right) + R_0 C_0 (3f + 3)$$

B: N/2-in NAND + NOR

$$t_{pB} = R_0 C_0 \left(\frac{N \left(\frac{N}{2} - 1 \right)}{4} + \frac{3N}{2} + 5f \right) + R_0 C_0 (3f + 6)$$

Mini assignment:

Assume $f = k$
 $N = ?$ @ crossover

Sweep N: Delay Comparison ($\beta = 2$)

N	t_{pA}	t_{pB}	$f = 3$	$f = 4$	$f = 5$
4	$21 + 6f$	$13 + 8f$	39 37	45 45	51 53
6	$36 + 6f$	$21 + 8f$	54 42	60 53	66 61
8	$55 + 6f$	$30 + 8f$	73 54	79 62	85 70
			A B	A B	A B

Min t_p : **don't build gates with fan-in > 4**

Transmission Gate Sizing

Try to make a TG with $R_{PD} = R_{PU}$

P:N ratio of k is not good for delay

- NMOS still has some pull-up strength (even if not all the way to V_{DD})
 - No need to have wide PMOS
- PMOS has some pull-down (but very weak)
 - PD slightly faster (NMOS is stronger)

TG Sizing: Some Common Numbers

2x penalty, weak transition

$$R_{N,DN} = R_0 \text{ k}\Omega\text{-}\mu\text{m} \mid R_{N,UP} = 2R_0 \text{ k}\Omega\text{-}\mu\text{m}$$
$$R_{P,UP} = 2.5R_0 \text{ k}\Omega\text{-}\mu\text{m} \mid R_{P,DN} = 5R_0 \text{ k}\Omega\text{-}\mu\text{m}$$

- Let's try $W_p = W_n$

- Parallel Up, $R_{TGUP} = R_{N,UP} \parallel R_{P,UP} = 1.1R_0$ Slightly faster

- Parallel Down, $R_{TGDN} = R_{N,DN} \parallel R_{P,DN} = 0.83R_0$

↑ for transmission gate

- So, **using $W_p/W_n = 1$ is fairly reasonable**

- Actual size may depend on the process technology

Delay Analysis (So Far): Summary

- **Device R and C determine circuit performance**
- **Elmore Delay approximation: initial insight into design**
 - Step response, does not account for signal slopes
 - Need slope correction [see slide 2.63]
- **The sizing of the transistors (a first glimpse)**
 - Determines V_M
 - Determines R_{DRV} as well C_{Load} it presents to the preceding gate which effects the delay
- **Large fan-in gates:**
large self-loading and loading to the preceding gate
 - Split into 2 gates when fan-in > 4

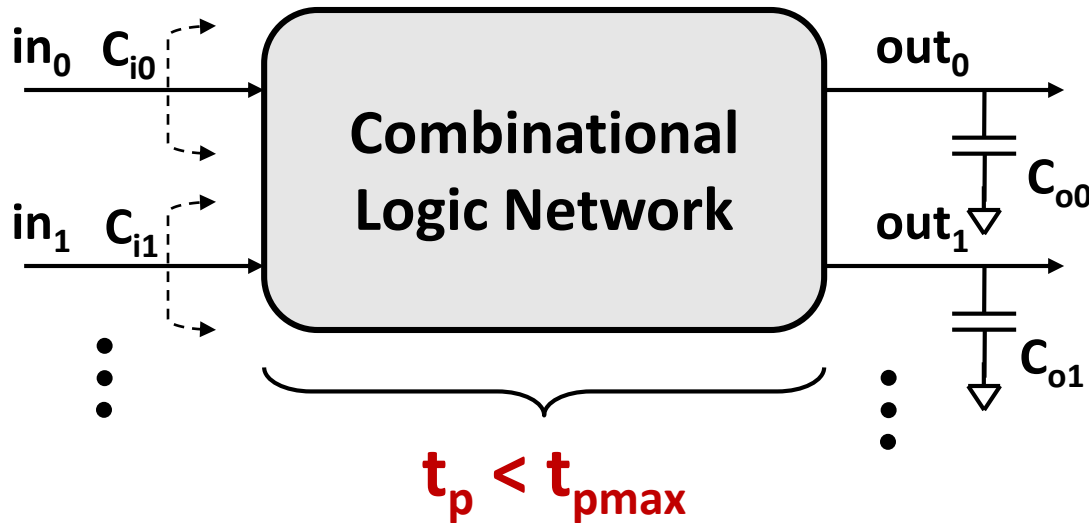
Speed Optimization via Gate Sizing

- **Gate sizing basics**
 - P:N ratio
 - Complex gates
 - Velocity saturation
 - Tapering



- **Developing intuition**
 - Number of stages vs. fanout
 - Popular inverter chain example

Problem Statement



- **Constraints:**

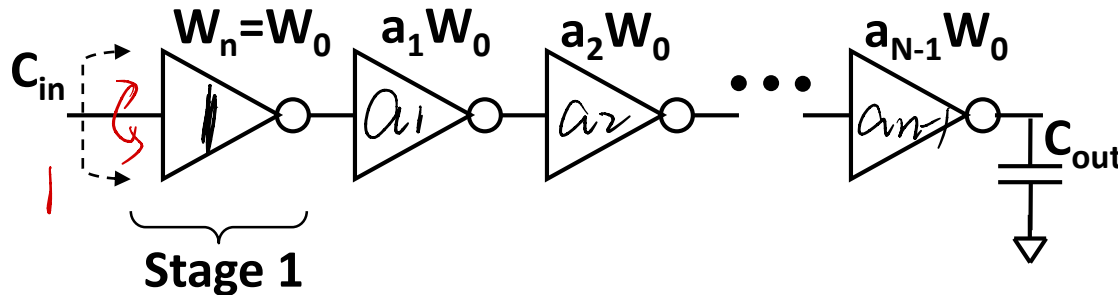
- C_{out} (load)
- C_{in} (driver load)
- Max delay

- **Given:**

- Arbitrary logic function
- Gate-level implementation

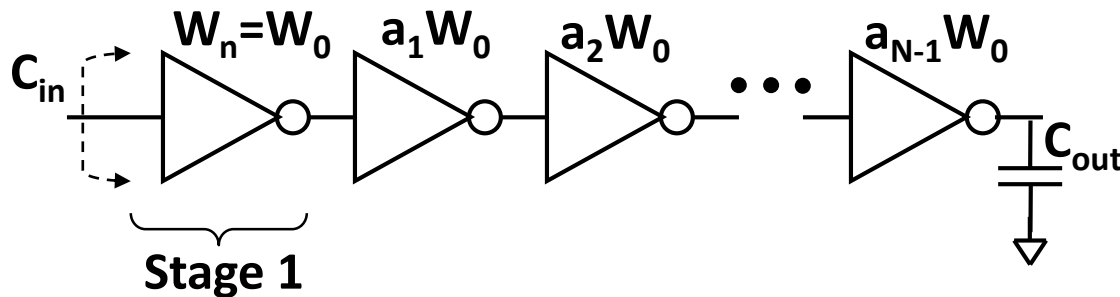
- **How do we decide the relative size of each gate?**

Simplified Problem: Buffering



- Assume: $\beta = k$
 - R_0 = Pull down for NMOS with size W_0 or PMOS with size βW_0
 - C_0 = Gate capacitance of N+PMOS of size $W_0, \beta W_0$
 - Ignore Source/Drain & Wire Capacitance for now
 - $\tau_0 = R_0 C_0$
- Goal: find $a_1, a_2, \dots, a_{N-1}$ to minimize delay

Delay Calculation



ignore C_{par} : $a_1 + \frac{a_2}{a_1} + \dots + \frac{a_k}{a_{k-1}} + \dots + \frac{C_{out}}{a_{out-1}}$

- Delay of stage 1: $a_1 C_0 R_0 = a_1 \tau_0$

- Delay of stage 2: $a_2 C_0 R_0 / a_1 = a_2 / a_1 \tau_0$

⋮

$$\frac{\partial}{\partial a_k} = \frac{1}{a_{k-1}} = \frac{a_{k+1}}{a_{k-2}} \Rightarrow$$

$$a_k = \sqrt{a_{k-2} a_{k+1}}$$

Optimal Fanout for Given N

- Fanout calculation:

- Stage 1 = a_1 , Stage 2 = a_2 / a_1

每个stage一致
↑

- Assuming that the **fanout of each stage is equal**, a_0

- $a_1 = a_0, a_2 = a_0^2, a_3 = a_0^3$

- $C_{out} = C_0 a_0^N$

- Total Delay = Sum (Delay of stage 1:N)

- Delay = $\tau_0 N a_0$

- Since ~~$C_{in} = C_0$~~

- $C_{out} / C_{in} = a_0^N$

↓ ↓ we know



$$a_0 = \left(\frac{C_{out}}{C_{in}} \right)^{\frac{1}{N}}$$

Optimum Number of Stages

For an arbitrary N:

$$N = \frac{\ln\left(\frac{C_{out}}{C_{in}}\right)}{\ln(a_0)}$$

To a_0 N

Min delay:

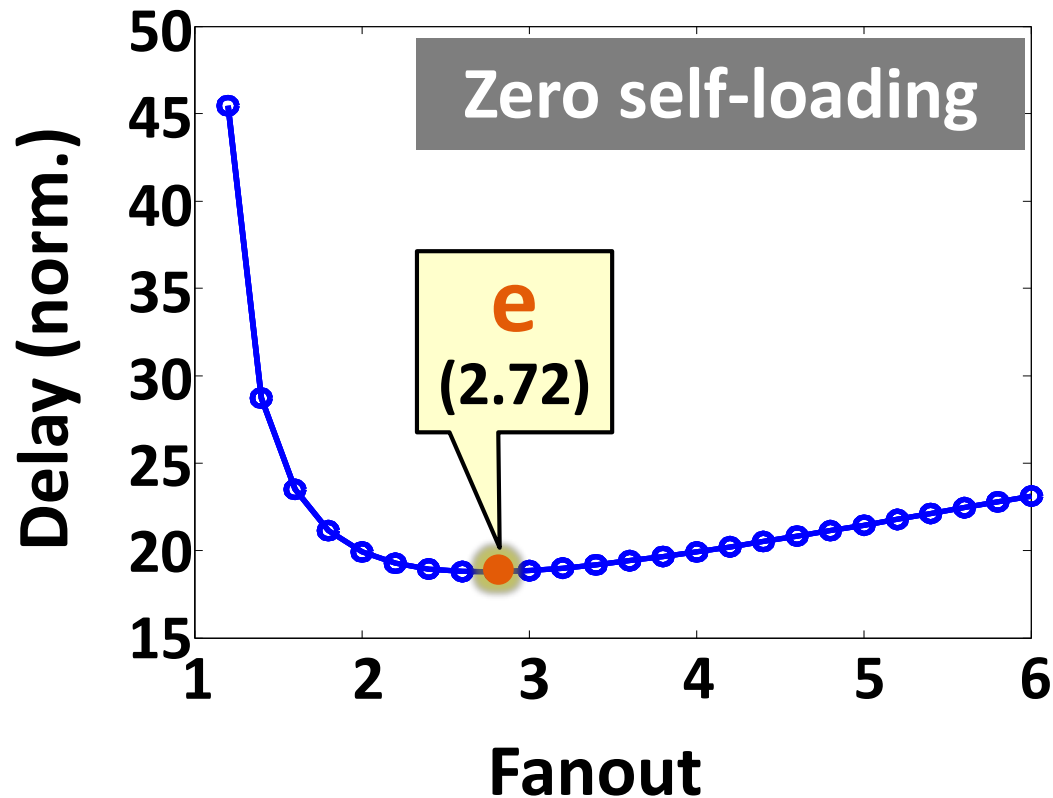
$$\frac{\partial Delay}{\partial a_0} = \frac{\partial \left[\tau_0 a_0 \frac{\ln\left(\frac{C_{out}}{C_{in}}\right)}{\ln(a_0)} \right]}{\partial a_0} = 0$$

$$\frac{\partial Delay}{\partial N} \frac{1}{\tau_0} = \left(\frac{C_{out}}{C_{in}}\right)^{\frac{1}{N}} - \frac{\left(\frac{C_{out}}{C_{in}}\right)^{\frac{1}{N}} \ln\left(\frac{C_{out}}{C_{in}}\right)}{N} = 0$$



$$a_0 = e$$

Optimum Number of Stages

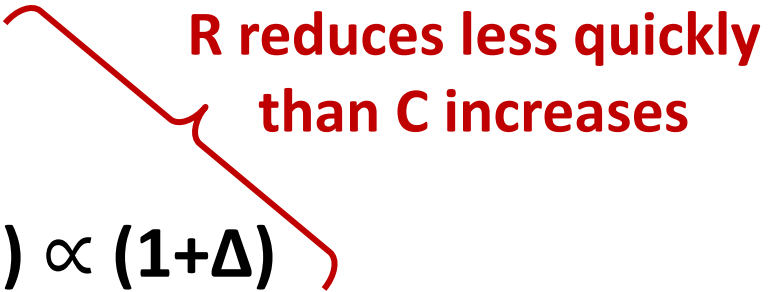


Set number of stages to reach optimal fanout

Constant Fanout Per Stage?

Intuition:

What if we increase the size of a stage by $(1+\Delta)$?

- $R_{\text{DRV}} \propto 1/(1+\Delta)$
 - $C_{\text{Load}} (\text{previous stage}) \propto (1+\Delta)$
- 
- R reduces less quickly than C increases

Delay is summed and **would increase**

(Constant FO) Mathematically

- Delay = $\tau_0(a_1 + a_2/a_1 + a_3/a_2 + a_4/a_3 + a_5/a_4 + \dots)$
- $d\text{Delay}/da_1 = 0$
 - $d\text{Delay}/da_1 = \tau_0(1 - a_2/a_1^2)$
 - So $a_1^2 = a_2$
- $d\text{Delay}/da_2 = 0$
 - $d\text{Delay}/da_2 = \tau_0(1/a_1 - a_3/a_2^2)$
 - So $a_2^2 = a_1 a_3$, thus $a_1^3 = a_3$



Min delay: equal fanout

Optimal Buffering with Self-Loading

- Intuition: **without** self-loading

- Delay decreases proportional to the decrease in N
- But increasing fanout increases delay proportionally
- The two are **equal @ the optimal N and fanout**

- Intuition: **with** self-loading

- Increasing FO no longer increases delay proportionally
 - Delay = $R_0(FO \cdot C_0 + C_{\text{par}})$
- **New N would be less and FO is bigger**

(Buffering with Self-Loading) Mathematically

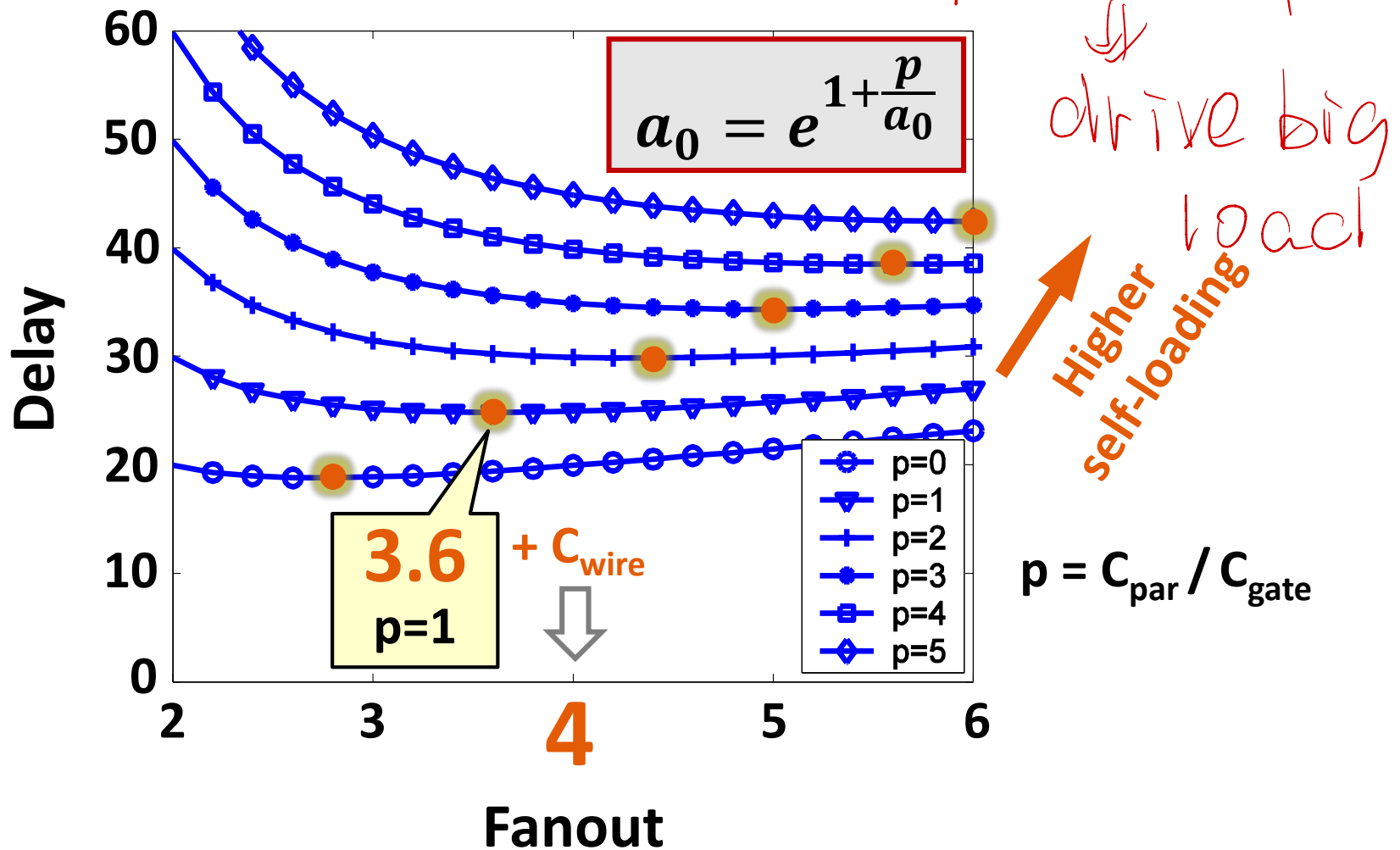
All equations remain the same except Delay

$$\frac{\partial Delay}{\partial a_0} = \frac{\partial \left[\tau_0 \left(a_0 + \frac{C_{par}}{C_0} \right) \frac{\ln \left(\frac{C_{out}}{C_{in}} \right)}{\ln(a_0)} \right]}{\partial a_0} = 0$$

$$\Rightarrow a_0 = e^{1 + \frac{p}{a_0}}$$

Optimal Buffering as fn (Self-Loading)

- A reasonable choice for optimal delay is **fanout of 4**

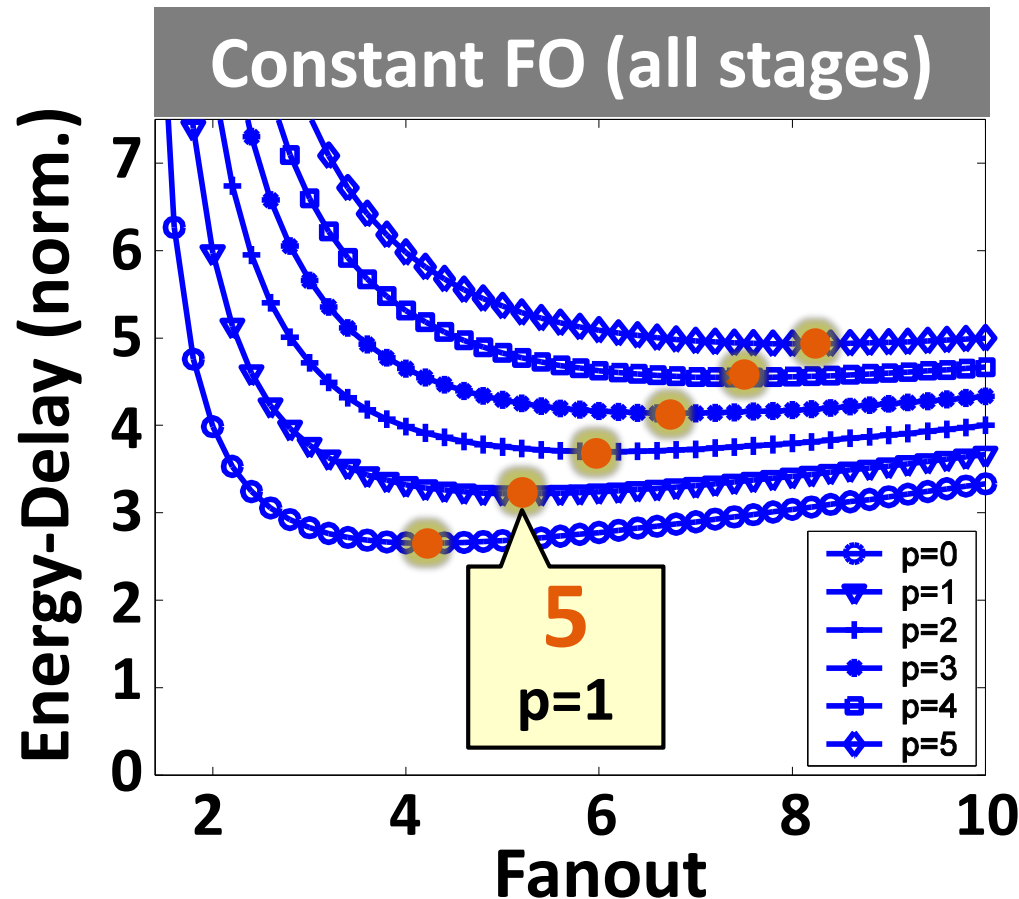


Optimal FO for

$$t_p > t_{p,\min}$$

Buffer Optimization for Energy-Delay

- Minimizing for Energy is trivial: min gate size
- Instead minimize Energy-Delay product



Result: larger FO

FO = 5 is pretty reasonable

Issue with Optimal Energy-Delay

- Constant fanout is not a good assumption

只需要最后

- Intuition:

↑ largest part.

part FO 大一点
前面 part

- Size of the final stage matters the most (use max fanout)
- Reduce fanout of prior stages to compensate...

可以小一点

- Example: $C_{in} = 1$, $C_{out} = 1000$, 4 gate stages

Design	Gate 1	Gate 2	Gate 3	Gate 4	EDP
$C_{in} \mid \text{FO}$	1 5.6	5.6 5.6	31.6 5.6	177.8 5.6	32200
$C_{in} \mid \text{FO}$	1 4.8	4.8 4.9	23.1 5.4	124.5 8.0	31100

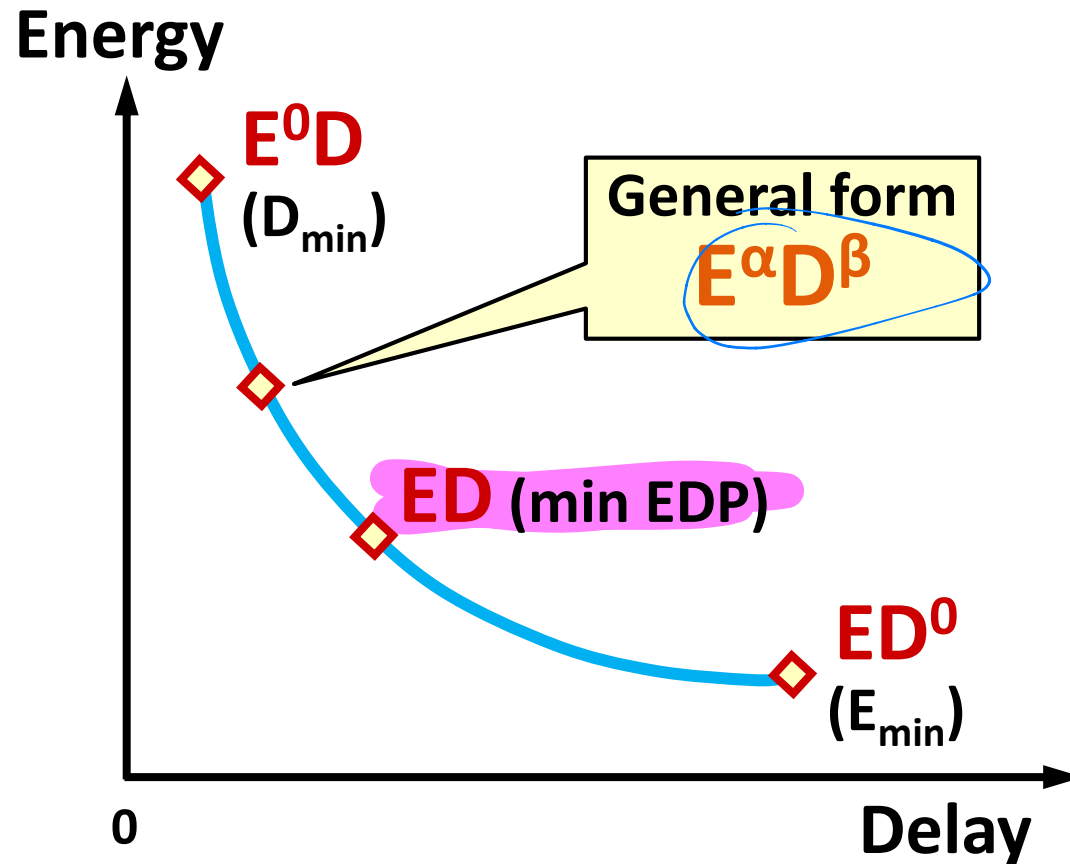
Tapered fanout reduces EDP

What if Fanout is Low?

- **Example:** large N (each stage drives small fanout)
 - Delay is logic limited, so reduce N
 - Balance Fanout so that they are equal
- **Try to adjust N such that each stage has $FO \sim 4$**
 - More complex logic for smaller N
- **OK, but not very systematic...**
 - Logical effort (next lecture) to formalize sizing

Energy-Delay Optimization (Lecture 14)

Variables: Gate size, Supply Voltage, Threshold Voltage



Summary

- **Delay of a logic network depends significantly on the relative size of logic gates**
 - Not transistors within a gate
- **Inverter buffering is a simple example of the analysis**
 - The analysis leads to $FO \sim 4$ as being optimal fanout for driving larger capacitive loads
 - The number of stages is optimized when $FO \sim 4$
 - For delays longer than minimum, tapered FO works best for minimizing power (more on this in Lec 14)